



제 30회 한국반도체학술대회

The 30th Korean Conference on Semiconductors

2023년 2월 13일(월)~ 15일(수) | 강원도 하이원리조트(그랜드호텔 컨벤션타워)

2023년 2월 15일(수), 09:00-10:30

Room B (에메랄드 II+III, 5층)

D. Thin Film Process Technology 분과

[WB1-D] Thin Films Transistors I

좌장: 박민혁 교수(서울대학교), 백인환 교수(인하대학교)

<p>WB1-D-1 09:00-09:15</p>	<p>Influence of RF Power in the Sputter-deposition of Amorphous InGaZnO Film on Transient Drain Current of Amorphous InGaZnO Thin-film Transistors Da Yeon Lee, Jingyu Park, Sangwon Lee, Seung Joo Myoung, Sung-Jin Choi, Jong-Ho Bae, Dong Myong Kim, and Dae Hwan Kim <i>School of Electrical Engineering, Kookmin University</i></p>
<p>WB1-D-2 09:15-09:30</p>	<p>Interface Improvement in Thin Film Transistors of Atomic Layer Deposited High-k/SnO Seung Ho Ryu^{1,2}, Jihoon Jeon^{1,2}, Taeyong Eom³, Taek-Mo Chung³, In-Hwan Baek⁴, and Seong Keun Kim^{1,2} ¹<i>KU-KIST Graduate School of Converging Science and Technology, Korea University,</i> ²<i>Electronic Materials Research Center, KIST,</i> ³<i>Thin Film Materials Research Center, KRICT,</i> ⁴<i>Inha University</i></p>
<p>WB1-D-3 09:30-09:45</p>	<p>8-inch Wafer Scale a-IGZO TFTs Applicable to NO₂ Gas Sensors Jeonghee Ko¹, Yongwoo Lee¹, Hanbin Lee¹, Yulim An¹, Hyo-In Yang¹, Dong Myong Kim¹, Dae Hwan Kim¹, Jong-Ho Bae¹, Min-Ho Kang², and Sung-Jin Choi¹ ¹<i>School of Electrical Engineering, Kookmin University,</i> ²<i>Department of Nano-process, NNFC</i></p>
<p>WB1-D-4 09:45-10:00</p>	<p>Electro-Photo-Controlled InTiO Synaptic TFTs with Graded AlSiO_x Gate Dielectric Chohyeon Park^{1,2} and Jung Wook Lim^{1,2} ¹<i>ETRI,</i> ²<i>University of Science and Technology (UST)</i></p>
<p>WB1-D-5 10:00-10:15</p>	<p>Comparative Study on Cation Composition-Dependent Contact Property of Thin-Film Transistors Using Atomic-Layer Deposited In-Ga-Zn-O Channel Dong-Hee Lee¹, Young-Ha Kwon², Nak-Jin Seong², Kyu-Jeong Choi², Gyungtae Kim³, and Sung-Min Yoon¹ ¹<i>Kyung Hee University,</i> ²<i>NCD Co., Ltd.,</i> ³<i>NNFC</i></p>
<p>WB1-D-6 10:15-10:30</p>	<p>A Study on the Correlation and Mechanism between Hydrogen Introduction and Improvement of Electrical Properties in InGaZnO Thin Film Transistor Hee Yeon Noh, Jung-Hwa Cha, June-Seo Kim, Myoung-Jae Lee, and Hyeon-Jun Lee <i>Division of Nanotechnology, DGIST</i></p>